

Title (en)

METHOD FOR PRODUCING A SURFACE THAT IS NOT COMPLETELY CERAMIC

Title (de)

VERFAHREN ZUR ERZEUGUNG EINER NICHT-VOLLKERAMISCHEN OBERFLÄCHE

Title (fr)

PROCÉDÉ POUR RÉALISER UNE SURFACE PAS ENTIÈREMENT CÉRAMIQUE

Publication

EP 2885442 A2 20150624 (DE)

Application

EP 13752610 A 20130813

Priority

- DE 102012107440 A 20120814
- EP 2013066891 W 20130813

Abstract (en)

[origin: US2015217596A1] A method of producing a ceramic-like surface (22) with sensory properties of the ceramic material on a substrate 10, comprising the following steps: Preparing at least one surface (12) of the substrate (10), Coating the prepared substrate surface (12) with a ceramic-like sensory layer (20) using a vapor-phase deposition method.

IPC 8 full level

C23C 14/02 (2006.01); **C23C 14/14** (2006.01); **C23C 16/02** (2006.01); **C23C 16/06** (2006.01)

CPC (source: EP US)

B44F 11/06 (2013.01 - US); **C23C 14/0015** (2013.01 - EP US); **C23C 14/024** (2013.01 - US); **C23C 14/028** (2013.01 - EP US); **C23C 14/0611** (2013.01 - US); **C23C 14/14** (2013.01 - US); **C23C 14/24** (2013.01 - US); **C23C 16/006** (2013.01 - EP US); **C23C 16/0254** (2013.01 - EP US); **C23C 16/0272** (2013.01 - US); **C23C 16/06** (2013.01 - US); **C23C 16/27** (2013.01 - US)

Citation (search report)

See references of WO 2014026974A2

Citation (examination)

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- "Handbook of Physical Vapor Deposition (PVD) Processing", 1 January 2010, ELSEVIER, ISBN: 978-0-8155-2037-5, article DONALD MATTOX: "Handbook of Physical Vapor Deposition (PVD) Processing", pages: 57 - 62, XP055670112

Designated contracting state (EPC)

AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

Designated extension state (EPC)

BA ME

DOCDB simple family (publication)

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DOCDB simple family (application)

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